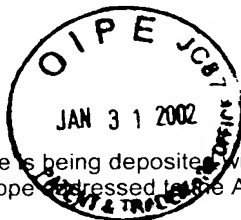


Docket No.: Z&PINFN10277



I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231, on the date indicated below.

By: [Signature]

Date: January 24, 2002

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Walter Hartner et al.
Applic. No. : 10/027,533
Filed : December 26, 2001
Title : Method for Fabricating a Precious-Metal Electrode

INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner of Patents and Trademarks,
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

United States Patent No. 5,130,172 (Hicks et al.), dated July 14, 1992;

United States Patent No. 5,296,255 (Gland et al.), dated March 22, 1994;

United States Patent No. 5,320,978 (Hsu), dated June 14, 1994;

United States Patent No. 5,403,620 (Kaesza et al.), dated April 4, 1995;

United States Patent No. 5,440,173 (Evans, Jr. et al.), dated August 8, 1995;

United States Patent No. 5,789,320 (Andricacos et al.), dated August 4, 1998;

United States Patent No. 5,807,788 (Brodskey et al.), dated September 15, 1998;

United States Patent No. 5,824,563 (Hwang), dated October 20, 1998;

German Published, Non-Prosecuted Patent Application DE 198 48 444 A1 (Kang et al.), dated December 23, 1999, selective metal layer production method and method for producing capacitors and contact hole fillings using said method;

European Patent Application EP 0 567 878 A1 (Huffman), dated November 3, 1993;

Ziling Xue et al.: "Organometallic Chemical Vapor Deposition of Platinum Reaction Kinetics and Vapor Pressures of Precursors", Chem. Mater. 1992, No. 4, pp. 162-166;

Ju-Hong Kwon et al.: "Preparation of Pt thin films deposited by metalorganic chemical vapor deposition for ferroelectric thin films", Thin Solid Films, Vol. 3, 1997, pp. 136-142;

Tomonori Aoyama et al.: "Chemical Vapor Deposition of Ru and Its Application in (Ba, Sr)TiO₃ Capacitors for Future DRAM", International Conference on Solid State Devices and Materials, Japan Society of Applied Physics, Tokyo, September 1998, pp. 44-45;

B.S. Kwak et al.: "Study of epitaxial platinum thin films grown by metalorganic chemical vapor deposition", Journal of Applied Physics, October 15, 1992, Vol. 72, No. 8, pp. 3735-3740;

Alfred A. Zinn et al.: "Metal CVD", chapter 7, "Chemical Vapor Deposition of Platinum, Palladium and Nickel", VCH-Weinheim, 1994, pp. 329-355;

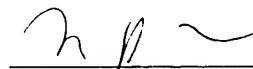
International Search Report dated November 15, 2000.

If no translation of pertinent portions of any foreign language patents or publications mentioned above is included with the aforementioned copies of those applications,

patents and/or publications, it is because no existing translation is readily available to the applicant.

Respectfully submitted,

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For Applicants

Date: January 24, 2002

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